

PATTERN COMPENSATION TECHNIQUES FOR CHARGED PARTICLE LITHOGRAPHIC MASKS

Abstract of the Disclosure

A method of producing a particle beam mask and mask structures to allow for the use of dummy fill shapes. This invention overcomes distortion in by adding a dummy shape in unexposed regions and applying a blocking layer to cover the dummy shape. The blocking layer is comprised of an aperture or additional mask mounted close to the mask or can be added to the mask itself.

Figures